



innovations
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microelectronics

Extraction of CTH with pulsed measurements

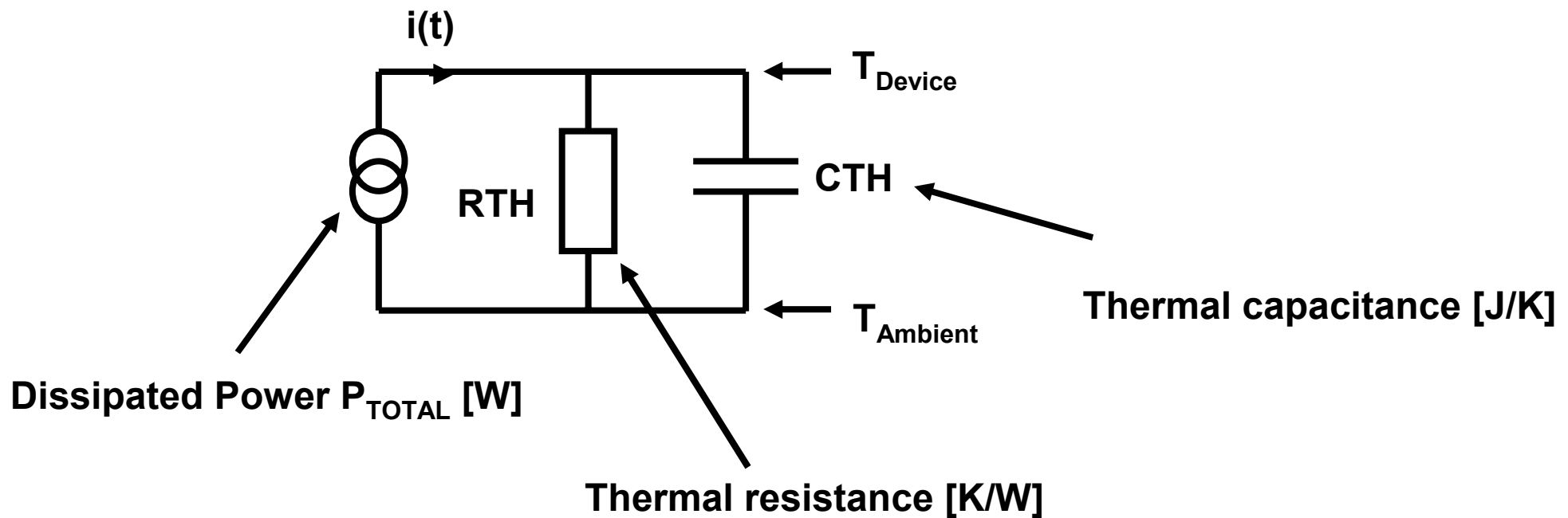
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- **Thermal network**
- **Measurement equipment**
- **Results**
- **Summary**

Simple Thermal network



for BJT/HBT:

$$P_{TOTAL}(t) = V_{CE}(t) \cdot I_C(t) + V_{BE}(t) \cdot I_B(t)$$

How to measure

- Thermal resistance R_{TH} can easily be measured with DC analyzer
- Thermal capacitance can be calculated from thermal time constant
- Thermal time constant is measurable with transient or quasi transient measurements

$$\tau_{th} = R_{TH} \cdot C_{TH}$$

$$C_{TH} = \frac{\tau_{th}}{R_{TH}}$$

Measurement equipment

- **DiVA 210 from Accent Opto**
- **dynamic I(V) analyzer**
- **Key features:**
 - 2 pulsed channels**
 - 100 ns – 1 ms pulse width**
 - 500 mA I_{\max}**
 - 10 V V_{\max}**
 - Pulsing from every DC BIAS point**
 - Quasi transient measurements possible**



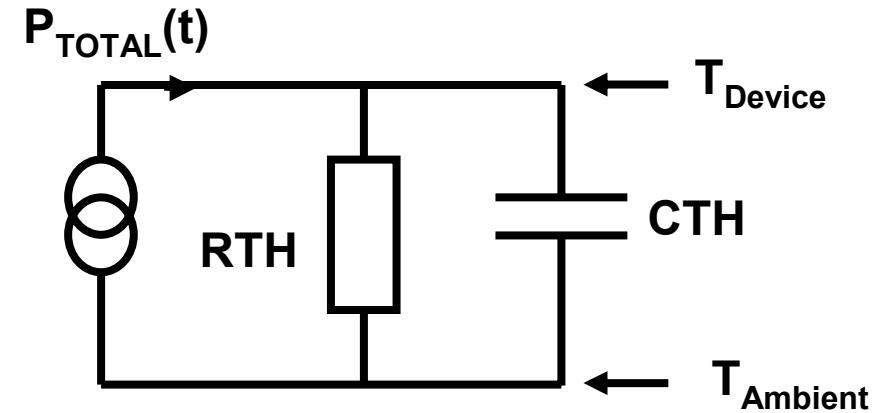
Assumptions

- only one thermal time constant
- only silicon has thermal capacitance
metallization and insulation is not taken into account
- Transistor is electrical fast
 $f_t > 500/t_{\text{pulse}}$ at pulsed BIAS point (5 GHz for 100 ns)
- Collector current is a linear function of temperature
- Power dissipation is constant over time
biggest simplification

Equations for Temperature



$$P_{TOTAL}(t) = CTH \frac{d\Delta T(t)}{dt} + \frac{\Delta T(t)}{RTH}$$



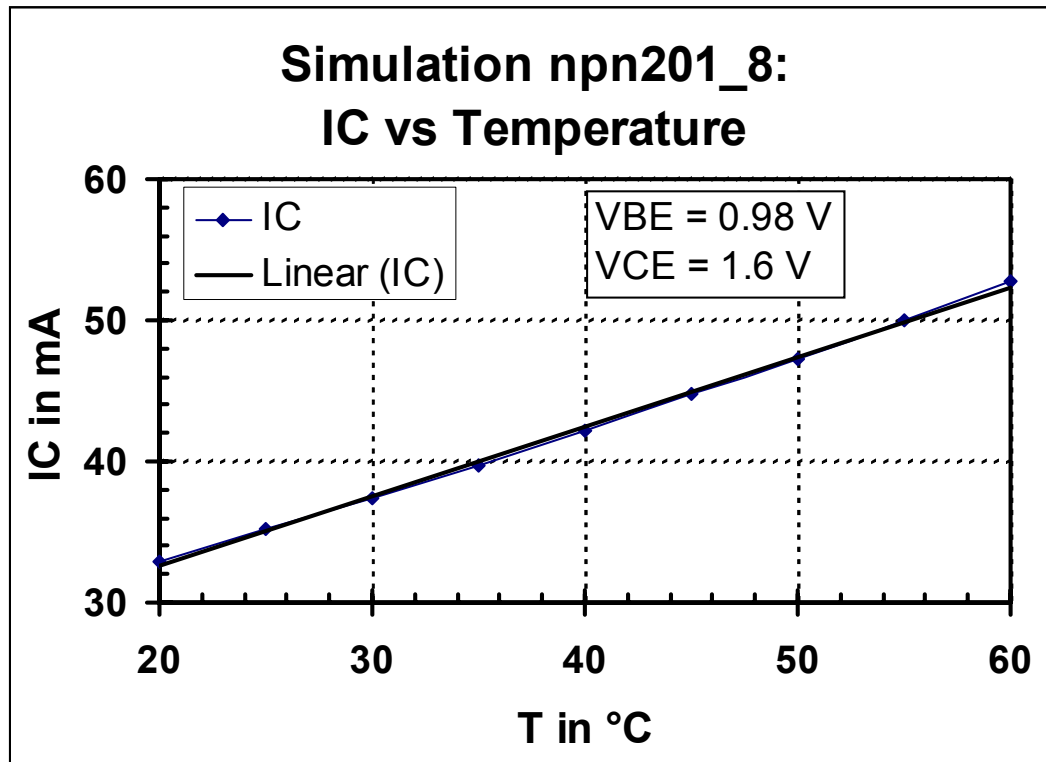
$$\Delta T(t) = P(t \rightarrow \infty) \cdot RTH \cdot \left(1 - \exp\left[-\frac{t}{\tau_{th}}\right] \right)$$

$$\Delta T = T_{Device} - T_{Ambient}$$

$$\tau_{th} = CTH \cdot RTH$$

Current vs. Temperature

- Temperature at device is unknown
can be measured indirectly over collector current



IC can be approximate as linear function of temperature:

$$I_C(T) = I_C(T_{NOM}) \cdot [1 + m \cdot (T - T_{NOM})]$$

$$\Delta T(t) = T(t) - T_{NOM}$$

$$I_C \sim T$$

Equations for Collector Current

- Temperature is replaced by current

$$I_C(t) = I_{C0} + X \cdot \left(1 - \exp\left[1 - \frac{t}{\tau_{TH}}\right]\right)$$

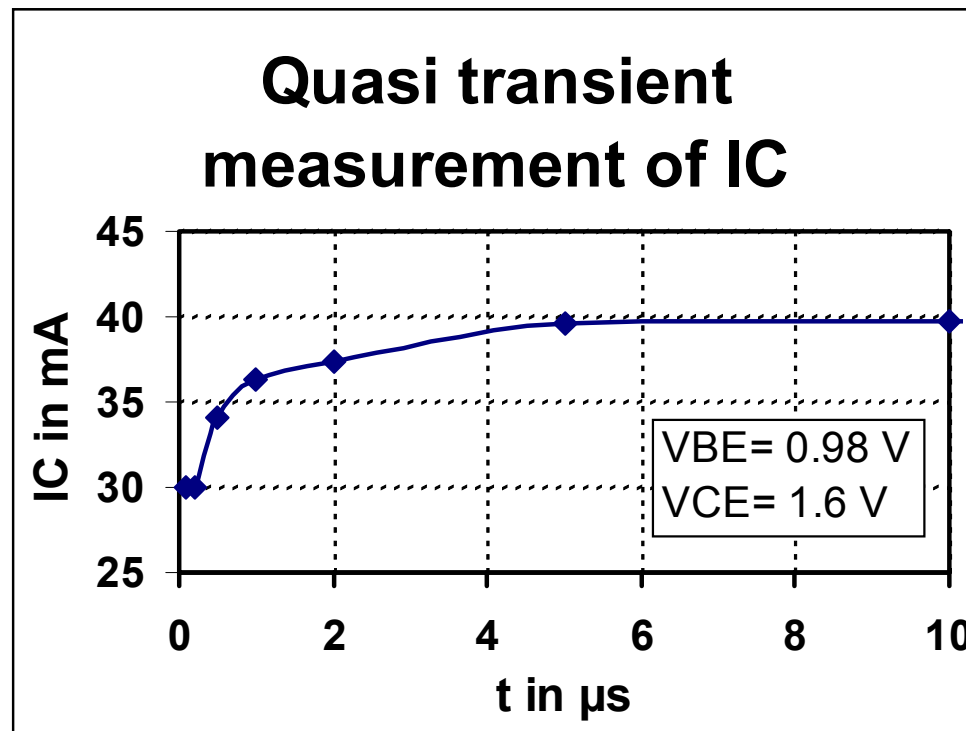
- IC0 and X are unknown
but IC at steady state is know

$$\ln(I_C(t \rightarrow \infty) - I_C(t)) = -\frac{1}{\tau_{TH}} \cdot t + \ln(X)$$
$$y = m \cdot x + b$$

- The slope contains the time constant

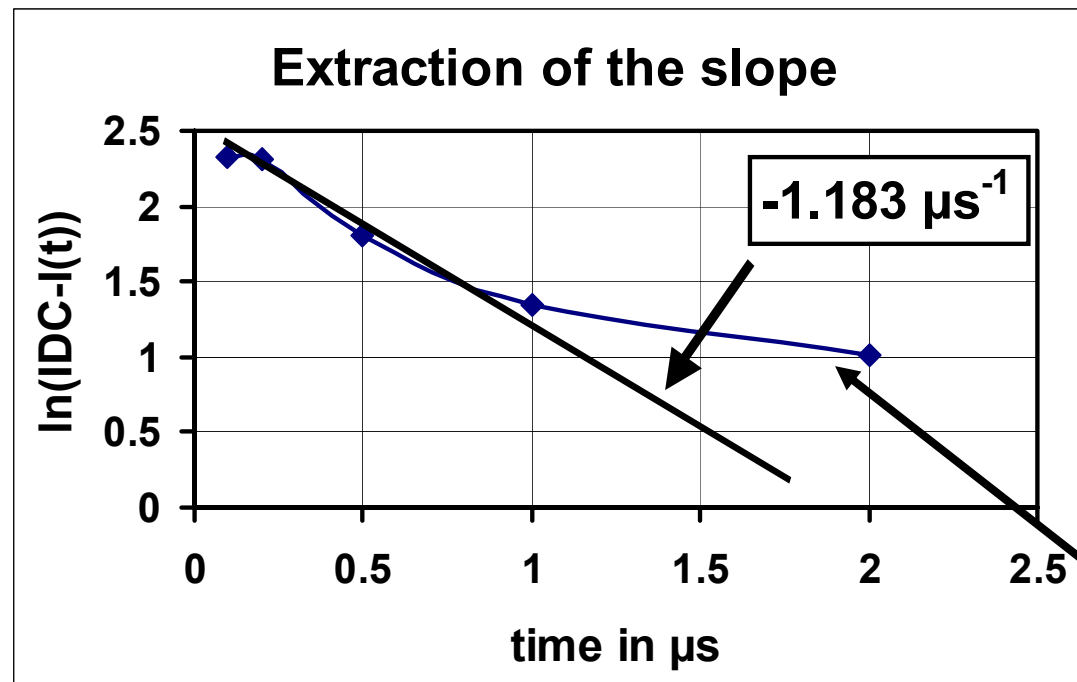
Measurement Results – IC

- Quasi transient measurement of an 8 emitter HBT
pulse conditions: $V_{BE} = 0.98 \text{ V}$, $V_{CE} = 1.6 \text{ V}$



Measurement Results – time constant

- Applying previous equations



second time constant
is visible

$$\tau_{TH} = -\frac{1}{m} \approx 0.85 \mu\text{s}$$

Measurement Results - CTH

- RTH of the transistor is known
CTH can be calculated

$$R_{TH} = 1980 \frac{K}{W}$$

$$\tau_{TH} \approx 0.85 \mu s$$

$$C_{TH} \approx 430 \frac{pJ}{K}$$

Confidence check

- Specific heat capacity and density of silicon are known
calculate the heated volume

$$\sigma_{Si} = 2330 \frac{\text{kg}}{\text{m}^3}$$

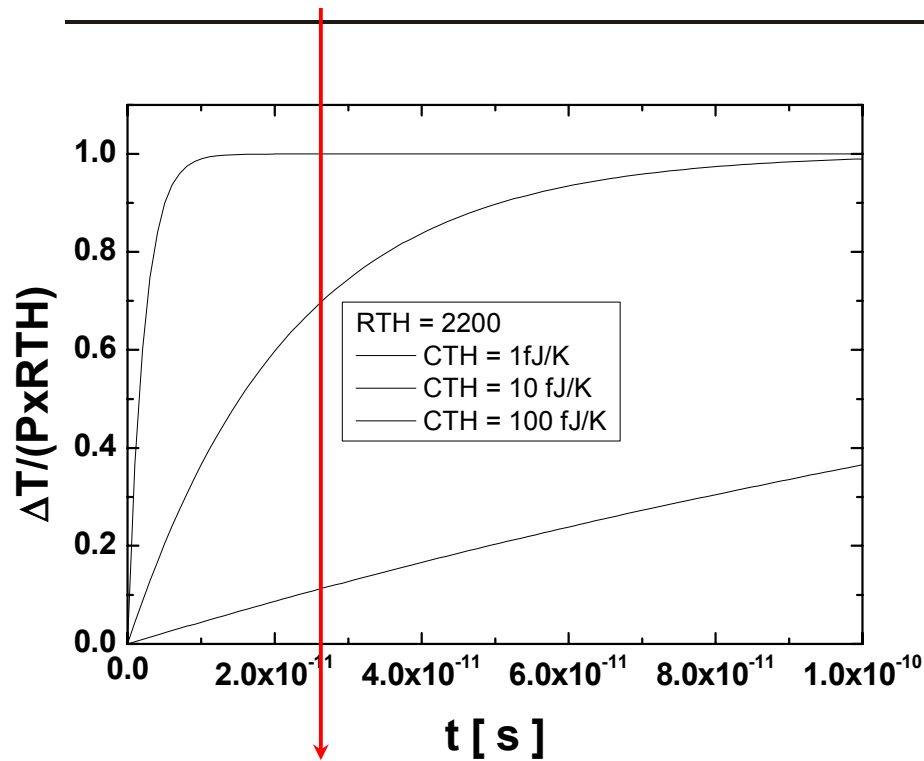
$$c_{Si} = 700 \frac{\text{J}}{\text{kg} \cdot \text{K}}$$

$$V_{heated} = \frac{CTH}{\sigma \cdot c}$$

$$\begin{aligned} V_{heated} &= 2.64 \cdot 10^{-16} \text{ m}^3 \\ &= 264 \mu\text{m}^3 \end{aligned}$$

**corresponds to a cube with 6.4 μm long sides:
reasonable result**

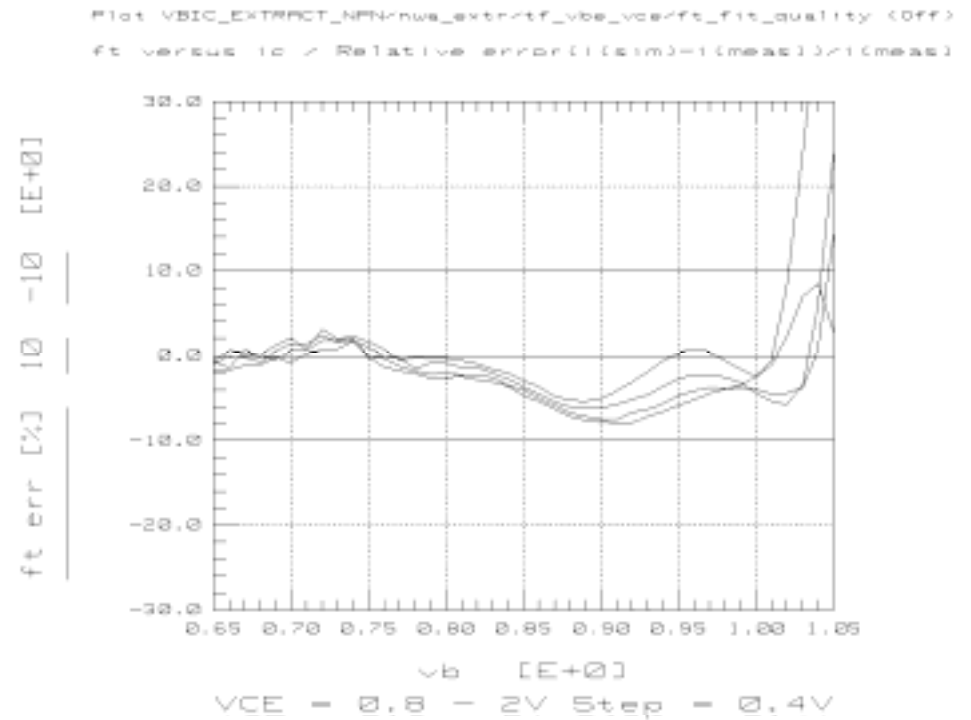
Influence of CTH on simulation



Measurement at 10 GHz, biggest influence on simulation if CTH ~ 5 – 20 fJ/K.

A CTH in pJ/K range influences the 100MHz frequency range

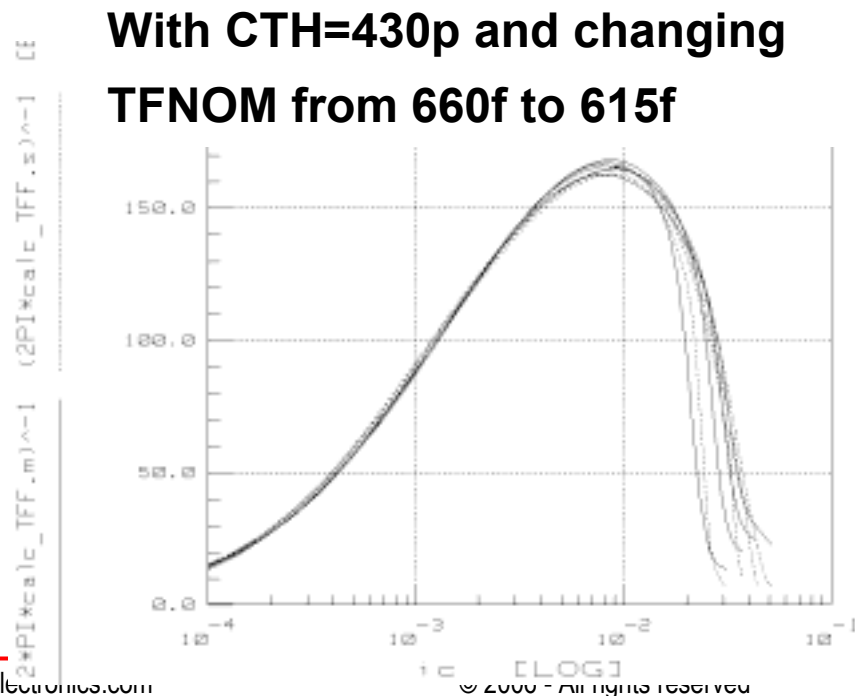
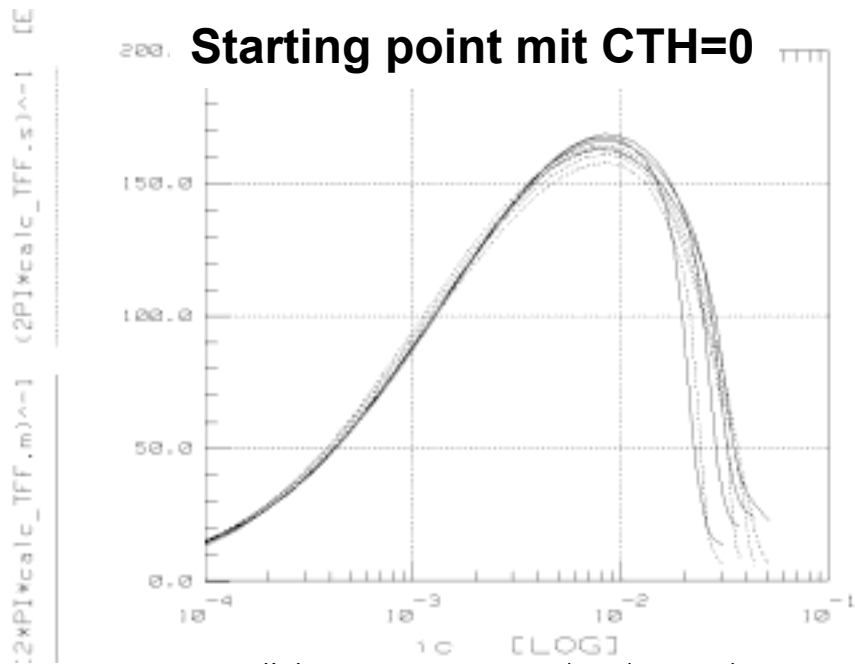
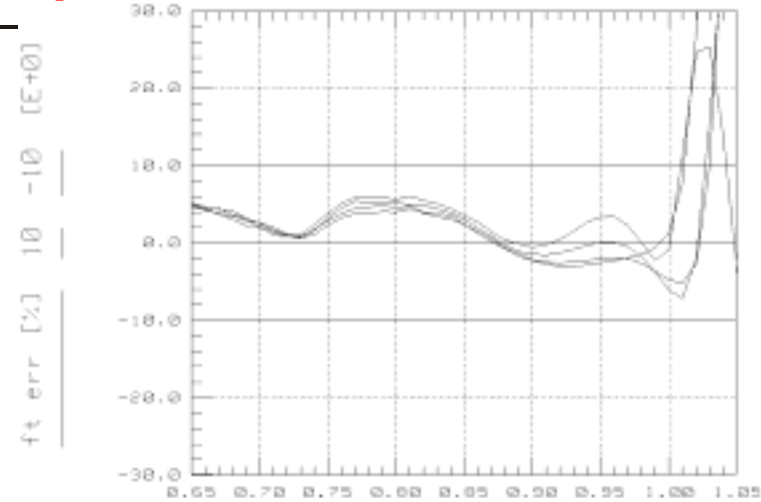
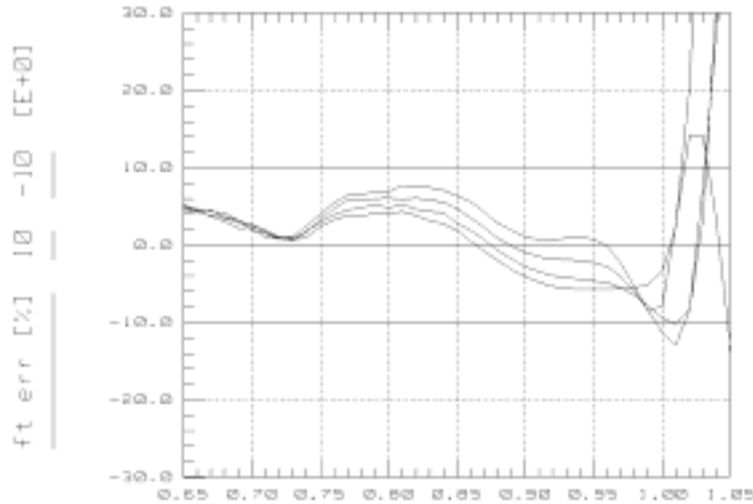
Influence of CTH on fT simulation:



CTH = 430p



Optimization of npn201 with CTH = 430p





Summary

- **Simple thermal network with corresponding equations was presented**
- **Results of quasi transient measurements were shown**
- **Step by step extraction of CTH including confidence check**
- **Influence of CTH on simulation was shown**